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Some Doping Effects on the Semiconducting Properties of Gd₂CuO₄

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Some doping effects on the semiconducting properties of the Gd_2CuO_4 compound were investigated. The ZrO_2 or ThO_2 (0.5 mol%) lowered the resistivity of the Gd_2CuO_4 at room temperature by a factor of 10^4 . The thermoelectric powers of the same samples were negative. These were explained as being due to the Cu^+ ions formed by the dopants. The CaO dopant lowered the resistivity by a factor of ten and converted the sign of the thermoelectric power from negative to positive. The resistivity of the BaO-doped samples increased with an increase in the dopant concentration up to 0.5 mol%, and decreased with an increase in the dopant concentration in the concentration region lower than that. This suggested that the dopant of BaO was less effective on the resistivity-lowering than was the CaO. The samples doped with the ZrO_2 and ZrO_3 simultaneously gave a trend similar to those doped with the BaO in the concentration dependence of the resistivity. Silver oxide and indium oxide were also employed as dopants, but no doping effects were observed on either resistivity or the lattice parameters.

The Ln₂CuO₄ compounds (Ln=Gd, Sm, Nd, and Pr) are semiconductive, and their resistivities increase with an increase in the atomic number of Ln.¹⁾ It has been suggested that the most important electron-carriers come from cuprous cations, Cu⁺, probably formed by a thermal decomposition of cupric cations,

Cu²⁺.¹⁾ The trend for the resistivities to increase with an increase in the atomic number of Ln was explained as being due to: (1) a variation in the number of the donor centers or (2) a variation in the activation energy.¹⁾ However, it is not known which factor is more important.

As is well known, some dopants introduce donor

¹⁾ T. Kenjo and S. Yajima, This Bulletin, 46, 1329 (1973).

centers.^{2,3,5,6)} If the dopants do not change the activation energy very greatly, any electrical effects due to the dopants can be ascribed to the first case. The X-ray diffraction data indicated that the lattice parameters for the Gd₂CuO₄ did not shift with doping, suggesting no variation in the activation energy. Therefore, the comparison of the doped to undoped Ln₂CuO₄ in the semiconducting properties may give an answer to the above problem.

Dopants usually lower the resistivity. Therefore, the most marked doping effect can be expected for the compound whose resistivity is the greatest. Since the Gd₂CuO₄ showed the greatest resistivity in the Ln₂CuO₄ series, it was chosen as the compound to be doped.

Donor centers are formed when the valence of the dopant is greater than that of the site.^{2,3,5,6)} Zirconium oxide, ZrO₂, and thorium oxide, ThO₂, were chosen as dopants which could be expected to occupy the Gd³⁺ sites, because they are chemically similar to the rare earth oxides.

Acceptor centers will be formed by dopants whose valences are smaller than those of the site. The most probable acceptor centers in this case are the Cu³+ or the Gd⁴+ cations. Since both of them are unstable and are not well known, it would be of interest to see if doped divalent cations lower the resistivity of the Gd₂CuO₄. Alkaline earth oxides are most suitable for the above purpose, because they are chemically similar to Gd₂O₃ and because they are expected to occupy the Gd³+ sites. Barium oxide, BaO, and calcium oxide, CaO, were employed as the dopants here.

Silver oxide, Ag₂O, and indium oxide, In₂O₃, were expected to occupy the Cu²⁺ sites and to form acceptor and donor centers respectively. They were also used as dopants.

Experimental

Reagents and Materials. An aqueous solution of Gd(NO₃)₃ was prepared by dissolving Gd₂O₃ (Nippon Yttrium Co., Ltd., 99.9%) in nitric acid (Wako Pure Chemical Co., Ltd., GR grade). The maximum contents of the impurities contained in the Gd₂O₃ used were Fe₂O₃, 10 ppm; CuO, 10 ppm; CaO, 30 ppm; ZrO₂, 10 ppm and ThO₂, 10 ppm.⁷⁾ An aqueous solution of Cu(NO₃)₂ was prepared by dissolving GR-grade Cu(NO₃)₂·3H₂O. The maximum contents of the impurities contained in the Cu(NO₃)₂ used were; Fe, 30 ppm; Zn, 50 ppm; Ni, 40 ppm; Ba, 20 ppm; Ca, 4.5 ppm; Zr, 10 ppm, and Th, not detected.8) The aqueous solutions of the nitrates of Zr, Ag, and Th were prepared by dissolving GR-grade ZrO(NO₃)₂, AgNO₃, and Th(NO₃)₄ respectively. The aqueous solutions of Ca(NO₃)₂, Ba(NO₃)₂, and In(NO₃)₃ were obtained by dissolving GR-grade CaCO₃, BaCO₃, and EP-

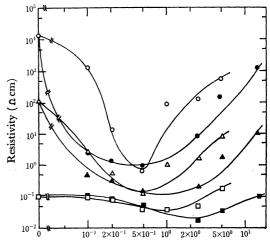
grade $\rm In_2O_3$ respectively in nitric acid. The concentration of the AgNO₃ solution was determined gravimetrically. The concentrations of the other solutions were determined chelatometrically against a standard EDTA solution.

The samples were prepared by the same method as in a previous work.1) Aliquot portions of Gd-(NO₃)₃, Cu(NO₃)₂, and the nitrate of the dopants were mixed, and a sodium hydroxide solution (1M) was stirred in. After the mixture had stood overnight, filtering-washing was repeated until no sodium ion was detected in the filtrate by the flame test. The mixed hydroxides thus obtained were dried at 120 °C and preheated at 750 °C for 4 hr in air. The lumped oxide mixtures were milled, pressed into 15-mm ϕ pellets, and heated at 1000 °C for 15 hr in air. The pellets thus obtained were removed from the furnace and cooled to room temperature. These samples thus obtained were cut into rods 12-13 mm long and 3-4 mm thick for the electrical measurements. The resistivity was measured by the 4-probe method using Du Pont No. 4622 Conductive Silver Coating Materials. The thermoelectric power was measured by means of the method of the previous work.1) The bulk densities of the samples thus obtained were essentially the same as those of the undoped Gd₂CuO₄.

Results

The concentrations of the dopants are expressed as a mol% of the dopants against the total moles of the Gd₂CuO₄ and the dopants used. The signs for the values of the thermoelectric power are the same as in the previous work, being positive for a p-type and negative for an n-type.

Figures 1, 2, 3, and 4 show the data for the ZrO₂-or ThO₂-doped Gd₂CuO₄. As will be described in a later section, the mole ratio of raw oxide mixtures was: Gd₂O₃: CuO: ZrO₂=1-x:1:x. The sample containing 5 mol% ZrO₂ gave only the X-ray diffraction pattern of the Gd₂CuO₄ phase, while the ZrO₂ phase was found for the sample containing 10 mol% ZrO₂. This indicated that the solubility of ZrO₂ in Gd₂CuO₄ was between 5 and 10 mol%.



Dopant concentration in Gd₂CuO₄ (mol%)

Fig. 1. Variation of resistivity with dopant concentration in $\mathrm{Gd_2CuO_4}$.

○: room temperature for ZrO₂-doping, △: 200 °C for ZrO₂-doping, □: 800 °C for ZrO₂-doping, ●: room temperature for ThO₂-doping, ▲: 200 °C for ThO₂-doping, ■: 800 °C for ThO₂-doping.

²⁾ G. H. Jonker, Philips Research Reports, 24, 1 (1969).

³⁾ T. Kawaguchi, "Handotai no Kagaku," Maruzen Co., (1971), p. 56.

⁴⁾ R. W. G. Wyckoff, "Crystal Structures," Vol. 3, Interscience Publishers, New York, N.Y. (1965) p. 68.

⁵⁾ Stephan P. Mittof, "Progress in Ceramic Science," Vol. 4, edited by J. E. Burke, Pergamon Press, p. 217.

⁶⁾ O. Kubaschewski and B. E. Hopkins, "Oxidation of Metals and Alloys," Butterworths, London (1967), p. 15.

⁷⁾ Private communication, Nippon Yttrium Co., Ltd.

⁸⁾ Private communication, Kanto Chemical Co., Ltd.

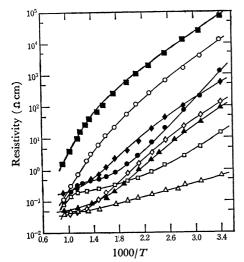


Fig. 2. Temperature dependence of resistivity for ZrO₂-doped Gd₂CuO₄.

○: undoped Gd_2CuO_4 , ♠: 0.1 mol%, □: 0.2 mol%, △: 0.5 mol%, ♠: 1 mol%, ◇: 2.5 mol%, ♠: 5.0 mol%, ■: less dense specimen of undoped Gd_2CuO_4

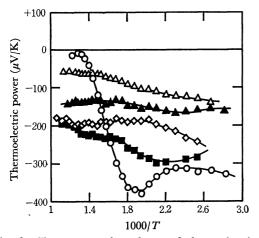


Fig. 3. Temperature dependence of thermoelectric power for ThO₂- or ZrO₂-doped Gd₂CuO₄.

 \bigcirc : undoped $\mathrm{Gd_2CuO_4}$, \diamondsuit : 0.5 mol% $\mathrm{ThO_2}$, \triangle : 15 mol% $\mathrm{ThO_2}$, \blacksquare : 0.5 mol% $\mathrm{ZrO_2}$, \triangle : 5 mol% $\mathrm{ZrO_2}$.

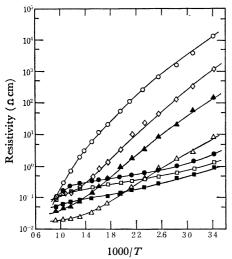


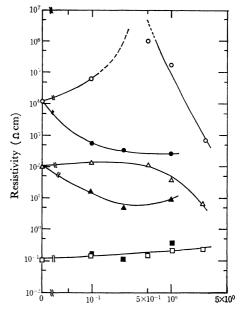
Fig. 4. Temperature dependence of resistivity for ${\rm ThO_2\text{-}doped}$ ${\rm Gd_2CuO_4}$.

 \bigcirc : undoped $\mathrm{Gd}_2\mathrm{CuO}_4$, \bullet : 0.1 mol%, \square : 0.2 mol%, \blacksquare : 0.5 mol%, \triangle : 2.5 mol%, \blacktriangle : 5 mol%, \diamondsuit : 15 mol%.

The resistivity, ρ , particularly at room temperature, decreases with an increase in the concentration of ${\rm ZrO_2}$ up to $0.5~{\rm mol\%}$. Beyond this concentration, however, the resistivity increases with an increase in the concentration of ZrO₂ (Fig. 1). Figure 2 shows the temperature dependence of the resistivity for the various contents of ZrO₂. The resistivity-lowering due to the dopant is the most marked at room temperature. The log ρ vs. 1/T plots for the samples of x < 0.5 mol %show shoulders in the high-temperature region. As is indicated by the black squares in Fig. 2, the resistivity of the less dense specimen is ten times that of the denser one (open circles); the bulk density of the former is 0.64 of the theoretical value, while that of the latter is 0.90 of the same value. The curves for the two specimens are parallel. Figure 3 indicates that the ZrO₂-doped Gd₂CuO₄ are *n*-type semiconductors.

The solubility of ThO₂ in the Gd₂CuO₄ was between 15 and 20 mol%. The ThO₂-doped samples are similar to the ZrO₂-doped ones in the dependence of the resistivity on the dopant concentration and in the thermoelectric power data; the resistivity is at a minimum at 0.5 mol% ThO₂, and the thermoelectric power is negative.

Figures 5, 6, and 7 give the data for the CaO- or BaO-doped Gd_2CuO_4 . The solubility of CaO in the Gd_2CuO_4 was between 1 and 5 mol%. Figure 5 shows that the resistivity decreases with an increase in the dopant concentration, but not so markedly as in the case of the ZrO_2 - or ThO_2 -doping. The $\log \rho \ vs.$ 1/T plots (Fig. 6) indicate that the ρ values for the CaO-doped samples, as well as their slopes, approach those for the undoped Gd_2CuO_4 in the high-temperature region. Figure 7 shows that the thermoelectric



Dopant concentration in Gd₂CuO₄ (mol%)

Fig. 5. Variation of resistivity with dopant concentration in $\mathrm{Gd}_2\mathrm{CuO}_4$.

○: room temperature for BaO, △: 200 °C for BaO-doping,
□: 800 °C for BaO-doping,
□: room temperature for CaO-doping,
▲: 200 °C for CaO-doping,
■: 800 °C for CaO-doping.

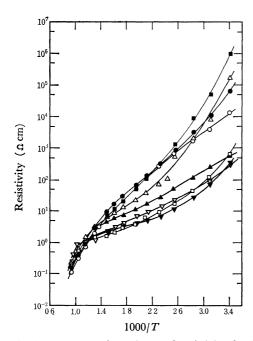


Fig. 6. Temperature dependence of resistivity for BaO- or CaO-doped Gd₂CuO₄.

○: undoped Gd₂CuO₄.

○: 0.1 mol% BaO, ■: 0.5 mol% BaO, ▲: 0.1 mol% BaO, ▲: 0.1 mol% CaO, ▲: 0.25 mol% CaO, △: 1 mol% CaO.

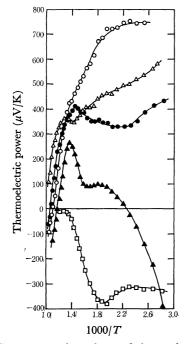


Fig. 7. Temperature dependence of thermoelectric power for CaO- or BaO-doped Gd₂CuO₄.

□: undoped Gd₂CuO₄, ○: 0.25 mol% CaO, △: 1 mol% CaO, ▲: 0.5 mol% BaO, ●: 2.5 mol% BaO.

power was changed from negative to positive values by doping the CaO.

The solubility of BaO in the Gd₂CuO₄ was between 2.5 and 5 mol%. The plots of the resistivity vs. the dopant concentration (Fig. 5) show the maximum resistivity value at 0.5 mol% BaO. Figure 6, showing the temperature dependence of the resistivity, is similar to the plots for the CaO-doped samples. The samples

containing large amounts of BaO give positive thermoelectric powers, except in the high-temperature region (Fig. 7). The sample containing 0.5 mol% BaO, the resistivity of which is the maximum (Fig. 5), changes its sign of the thermoelectric power at 180 and 580 °C.

Figures 8, 9, and 10 show the data for the Gd₂CuO₄ doped both with ZrO₂ and with CaO simultaneously with a constant total mole value of the ZrO₂ and CaO.

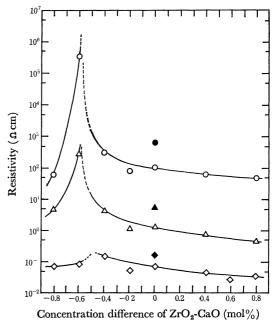


Fig. 8. Variation of resistivity with concentration difference, ZrO_2 -CaO, in Gd_2CuO_4 . \bigcirc : room temperature for ZrO_2 +CaO=1 mol%, \triangle : 200 °C for ZrO_2 +CaO=1 mol%, \diamondsuit : 800 °C for ZrO_2 +CaO=1 mol%, \spadesuit : room temperature for ZrO_2 +CaO=10 mol%, \spadesuit : 200 °C for ZrO_2 +CaO=10 mol%, \spadesuit : 800 °C for ZrO_2 +CaO=10 mol%.

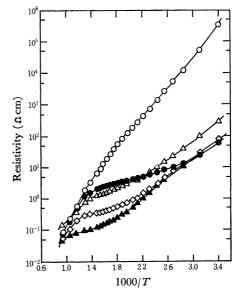


Fig. 9. Temperature dependence of resistivity for ZrO₂- and CaO-doped Gd₂CuO₄.

■: ZrO₂=0.1 mol%, CaO=0.9 mol%, ○: ZrO₂=0.2 mol

%, CaO = 0.8 mol%, $\triangle: ZrO_2 = 0.3 \text{ mol}\%$, CaO = 0.7 mol%, $\diamondsuit: ZrO_2 = 0.4 \text{ mol}\%$, CaO = 0.6 mol%, $A: ZrO_2 = 0.7 \text{ mol}\%$, CaO = 0.3% mol%.

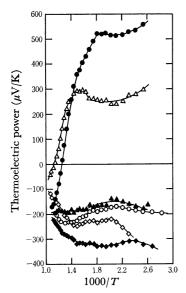


Fig. 10. Temperature dependence of thermoelectric power for $\rm ZrO_2$ - and $\rm CaO$ -doped $\rm Gd_2CuO_4$. \triangle : $\rm ZrO_2$ = 0.1 mol%, $\rm CaO$ =0.9 mol%, \blacksquare : $\rm ZrO_2$ =0.2 mol%, $\rm CaO$ =0.8 mol%, \diamondsuit : $\rm ZrO_2$ =0.3 mol%, $\rm CaO$ =0.7 mol%, \spadesuit : $\rm ZrO_2$ =0.4 mol%, $\rm CaO$ =0.6 mol%, \bigcirc : $\rm ZrO_2$ =0.5 mol%, $\rm CaO$ =0.5 mol%, $\rm A$: $\rm ZrO_2$ =0.6 mol%, $\rm CaO$ =0.4 mol%.

Figure 8 shows the dependence of the resistivity on the composition of ZrO₂-CaO in mol%. The ρ value is at its maximum at the concentrations of 0.2 and 0.8 mol% of ZrO₂ and CaO respectively. The CaO-and ZrO₂-rich samples show essentially the same trend as the CaO-doped and ZrO₂-doped samples respectively in the temperature dependence of their resistivities.

Discussion

The lattice sites occupied by a dopant can be estimated by the use of an X-ray diffractometer when the dopant concentration is higher than its sensitivity limit. When the ZrO₂, for example, is doped, the mole ratio of the raw oxide mixtures, CuO: Gd₂O₃: ZrO₂, is 1:1-x:x or 1-x:1:x, where x is the dopant concentration. The former ratio is used when the ${\rm ZrO_2}$ is expected to occupy the Gd3+ sites; the dopant in the latter case is expected to occupy the Cu²⁺ sites. If the ZrO₂ occupies the Gd³⁺ sites, the ZrO₂ phase will be found in the samples prepared in the latter fashion. If the ZrO₂ occupies the Cu²⁺ sites, the same phase will be found in the former samples. The X-ray diffraction data indicated that ZrO2 phase was present in the samples when $CuO: Gd_2O_3: ZrO_2=1-x:1:x$, and that no ZrO₂ phase was present when CuO: Gd_2O_3 : $ZrO_2=1:1-x:x; x<0.1$ for both cases. Consequently, the doped ZrO2 or the ThO2 was found to occupy the Gd3+ sites in the concentration region of 0.1>x>0.05.

The X-ray diffraction data described above still leave two problems: (1) it is not known which sites are occupied by the dopants in the x < 0.05 concentration region, and (2) a small amount of the $\rm ZrO_2$ or $\rm ThO_2$ may be present in the $\rm Cu^{2+}$ sites, although

an X-ray diffractometer does not detect them. It is difficult to give a clear answer to the above problems, but the following assumptions may be made: (1) the ZrO_2 or ThO_2 occupies the Gd^{3+} sites also in the $\kappa < 0.05$ concentration region, and (2) the fraction of the Cu^{2+} sites which might be occupied by the dopants is so small that the electrical effects due to them are negligibly small. The above two assumptions seem reasonable, because the sites occupied by the dopants are unlikely to depend upon the dopant concentration, and because the ZrO_2 or ThO_2 is chemically more similar to Gd_2O_3 than to CuO.

The doped Gd₂CuO₄ decreases in its resistivity with an increase in the concentration of ZrO₂ up to 0.5 mol%. This suggests the presence of donor centers. The doped Zr⁴⁺ cations occupy the Gd³⁺ sites and may be initially reduced to Zr3+ cations to minimize the strain energy due to the oxygen vacancies, but the Zr3+ cations formed, if they were fixed at the sites, do not act as donor centers because they are on the Gd³⁺ sites, where an appreciable electron-overlapping cannot be expected.1) The Cu⁺ ions, on the other hand, seem to be more probable donor centers, because they are on the Cu2+ sites, where an electron-overlapping can be expected.1) The Cu+ ions are formed by the reduction of the Cu2+ ions while the Zr3+ ions are oxidized to Zr⁴⁺ ions—that is, Cu²⁺+Zr³⁺=Cu⁺+ Zr⁴⁺. This reaction is an electron-transfer from the Zr3+ to Cu2+ ions, and results in excess positive and negative charges at the Zr⁴⁺ and Cu⁺ ion respectively. It is electrostatically unstable. However, the electrostatic energy needed for the electron-transfer is compensated for by the energy difference between the Cu+ formation and the excitation of the Zr3+ to the Zr⁴⁺ ion, because the Cu⁺ ion seems to be more stable than the Zr³⁺ ion.

The increase in the resistivity with the increase in the concentration of ZrO₂ beyond 0.5 mol% is unexpected. An increase in the resistivity is usually ascribable to a decrease in the number of carriers or to a decrease in the mobility.3,5,6) In this case, however, a decrease in the number of carriers is not likely, because such a doping effect as would decrease the number of carriers cannot be expected. A decrease in the mobility is not likely either, although the mobility might be lowered because of the electron scattering by the lattice vacancies. Therefore, some changes in the grain boundary are more likely to be causes of the above fact. As can be seen in Fig. 2, the less dense specimen is greater than the denser one in its resistivity, while the slopes in the log ρ vs. 1/T plots are the same. This is simply because the less dense sample is smaller than the denser one in the contacting area of the grains. The ZrO₂ dopant, on the other hand, enhances not only the resistivity but also the slopes of the plots. Therefore, a decrease in the contacting area of the grains, which is one of the changes in the grain boundary, is not a cause of the increase in the resistivity with the increase in the concentration of ZrO₂. Another possible change in the grain boundary would be a deposit of some insulators on the grain boundary. A small amount of ZrO₂, for example, one too small

to be detected by an X-ray diffractometer, might increase both the resistivity and the activation energy of the samples.

The previous work¹⁾ revealed that the resistivity of Ln₂CuO₄ decreases with a decrease in the atomic number of Ln. This fact was explained as being due to: (1) a variation in the activation energy, or (2) a variation in the number of the donor centers formed by the thermal decomposition of the Cu2+ to the Cu+ ions. However, it is not known which factor is the more important. The activation energy corresponds to the energy gaps between the split 3d-electron energy levels of the Cu2+ ions, which are affected by the ligandfield strength at the Cu2+ sites.1) The ligand-field strength is determined by the distance between the Cu²⁺ ions and the closest neighbors. Since no change is indicated in the lattice parameters of the doped Gd₂CuO₄, the distance described above may also be unchanged by doping. On the basis of the above discussion and the X-ray diffraction data, it seems reasonable to assume that the ligand-field strength at the Cu2+ sites is unchanged by doping; therefore, the doping method varies the number of donor centers without a great variation in the activation energy. The activation energy is related to the thermoelectric power by this equation: $\alpha \propto -E/T$, for the Maxwell distribution, where α is the thermoelectric power; E, the activation energy, and T, the temperature.^{1,3)} Therefore, the dopants are expected to lower the resistivity without a great variation in the thermoelectric power. In fact, Fig. 2 shows that the Gd₂CuO₄ doped with 0.5 mol\% ZrO₂ is lower than the Pr₂CuO₄¹⁾ in its resistivity, while the former is greater than the latter in its thermoelectric power. The $\alpha \propto -E/T$ relationship is applied to the data for the Ln₂CuO₄ compounds. If the trend for the resistivity of the Ln₂CuO₄ to decrease with a decrease in the atomic number of Ln was simply due to an increase in the number of donor centers, and not to a variation in the activation energy, the thermoelectric powers of the Ln₂CuO₄ compounds would not depend upon the atomic number of Ln. However, their thermoelectric powers increase with an increase in the atomic number of Ln,1) suggesting that the above trend is ascribable to an increase in the activation energy. The X-ray diffraction data seem to support this suggestion; the lattice parameter of the tetragonal Ln₂CuO₄, c/a, increases with a decrease in the atomic number of Ln.1,4)

Figure 5 shows that the resistivity decreases with an increase in the concentration of CaO, suggesting a formation of acceptor centers. It has been suggested on the basis of the X-ray diffraction results that the doped Ca²⁺ or Ba²⁺ ions occupy the Gd³⁺ sites. If they occupy the Gd³⁺ sites without oxygen vacancies, the doped alkaline earth cations would be forced to be in a trivalent state. Trivalent alkaline earth cations, however, are very unstable. The Cu²⁺ ions, on the other hand, seem to be more readily oxidized to Cu³⁺ ions, although the Cu³⁺ ions may still be unstable. As in the case of the Cu⁺ formation, the formation of the Cu³⁺ ions is an electron transfer from the Cu²⁺ ions to the Ca³⁺ ions which might be initially formed.

This electron-transfer is again electrostatically unstable. The electrostatic energy needed for the electron-transfer may be compensated for by the energy difference between the formation of the divalent alkaline earth cations and the excitation of the Cu²⁺ to Cu³⁺ ions. The Cu³⁺ ions would not be very stable, so many acceptor centers cannot be expected to be formed. This may be one of the reasons why the CaO-doping is not so effective on the resistivity-lowering as the ZrO₂- or ThO₂-doping. The presence of the acceptor centers is directly suggested by the positive thermoelectric power (Fig. 7).

The number of acceptor centers formed at a given dopant concentration is such a number as will minimize the total energy of the strain due to the oxygen vacancies and that of the excitation of the Cu2+ to Cu3+ ions. The strain energy may be made smaller by doping larger cations. Therefore, the number of acceptor centers formed at a given dopant concentration can be made smaller by doping larger cations. The experimental results for the BaO-doped Gd₂CuO₄ show the expected behavior (Figs. 5-7). The resistivity increases with an increase in the dopant concentration in the concentration region of x < 0.5 mol%. The sample doped with 0.5 mol% BaO shows a medium trend between the undoped and 2.5 mol% BaO-doped samples in the temperature dependence of the thermoelectric power. These data suggest that the donor centers initially formed by the thermal decomposition are recombined with the acceptor centers formed by doping the BaO, and that the former still number more than the latter. In concentration region of x < 0.5 mol%, the CaO-doped samples are p-type semiconductors and decrease in resistivity with an increase in the concentration of the CaO. These results indicate that the BaO dopant at a given concentration produces a smaller number of acceptor centers than the CaO dopant. In the concentration region of x>0.5 mol%, the BaO-doped samples behave much like the CaOdoped ones; the resistivity decreases with an increase in the concentration of BaO, and the thermoelectric power is positive, over the temperature range investigated. These facts suggest that the acceptor centers number more than the donor centers in this concentration region.

The recombination of the donors with the acceptors can be made by doping the ZrO_2 and CaO simultaneously. Since the donor centers consist of Cu^+ ions formed by the ZrO_2 -doping and those formed by the thermal decomposition of the Cu^{2+} ions, the dopant concentration where the resistivity is at its maximum will shift to a CaO-rich composition because of the donor centers formed by the thermal decomposition. Figure 8 shows the expected results; the maximum resistivity can be seen at CaO=0.8 mol% and $ZrO_2=0.2 \text{ mol}\%$. The thermoelectric power data correspond to the resistivity data; the sign is changed at the same concentration.

On the basis of the series of data shown in Figs. 5 to 10, it can be concluded that the most important donor centers in the Ln₂CuO₄ compounds are the Cu⁺ ions formed by the thermal decomposition of the Cu²⁺

ions.

An attempt to dope Ag_2O and In_2O_3 was unsuccessful. This failure may be partly due to too great a difference in the ionic radii between the Cu^{2+} ion and

either the Ag⁺ or the In³⁺ ion (Cu²⁺=0.72 Å, Ag⁺= 0.97 Å, and In³⁺=0.81 Å) and partly to too small a latitude of the Cu²⁺ site for the ionic size. This may be related to the covalent nature of the Cu–O bonds.